

**CVD for Research & Development**[EasyTube™ CVD Systems](#)[EasyTube™ 101](#)[EasyTube™ 2000](#)[EasyTube™ 3000](#)[EasyTube™ 4000](#)[EasyTube™ 6000](#)[EasyGas™ 1000](#)[EasyGas™ 1500](#)[EasyExhaust™](#)**CVD Process Development**[Application Lab](#)**CVD for Production**[ALD](#)[APCVD](#)[LPCVD](#)[TCO Deposition](#)[Cluster Tools](#)[MOCVD](#)[Reel to Reel](#)[Custom CVD](#)**CVD for Quality Control**[Si-Precursor Quality Control](#)**Gas/Liquid Delivery & Exhaust Solutions**[Gas Delivery](#)[Chemical Delivery](#)[Custom Chamber](#)[OEM Manufacturing](#)[eLine™ Express UHP Welding](#)[ePanel™ Express Gas Panels](#)[Stainless Steel UHP Bubblers](#)[✉ Forward to a Friend](#)**EasyTube™ 101 - Advanced CVD process development tool for the University or Industrial Researcher**

Wide Range of Process Capabilities



First Nano, a division of [CVD Equipment Corporation](#), introduces the new **EasyTube™ 101 system platform**. The EasyTube™ 101 is a user friendly, low cost, equipment/process solution for the researcher that has a limited budget and needs turn-key equipment with a baseline process recipe and proven safety system.

Your EasyTube™ 101 system can be configured [online](#) or together with an Application support engineer for your specific process needs and budget limitations. Give us a chance to send you a quote and you will see that a homemade system cannot match the VALUE and SAFETY of these novel entry level CVD systems.

We know that your process needs are likely to change as your research progresses and that your research budget is always constrained. That is why we designed this system for easy field upgrades and/or reconfiguration, thus enhancing the EasyTube™ 101 price/performance value. In the coming months, more process support information will be made available on our EasyTube™ product websites, thus providing increased support for our steadily growing worldwide EasyTube™ customer base. Please come back from time to time to find software updates, process recipes, application notes, results achieved by other customers, etc.

Each EasyTube™ 101 system can be configured or reconfigured (in the future) for a wide range of processes including ALD, APCVD, LPCVD, RTP, Annealing, Diffusion, etc. Most options and system reconfigurations can be added or installed in the field.

The EasyTube™ 101 is controlled by our proprietary real-time LabWindow™ based process control software CVDWinPrC™ that provides recipe driven process control, real-time graphing and automatic data logging for optimal process reproducibility. It also communicates with a PLC to manage the hardware interface and provide the appropriate industrial level safety systems and includes a standard Web interface for remote training, software upgrades, system reconfiguration, support and trouble shooting.

Before you decide that you can't afford a custom designed CVD system, give us a chance to show you what we can do for you. You could get so much system (and safety) for so little money.

Our other divisions, [CVD](#) and [SDC](#) supply a wide range of Chemical Vapor Deposition Equipment, Processing Solutions and gas delivery systems to the industry and research market. More information is available at www.cvdequipment.com.

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